

Form 1449 (Modified)		Atty Docket No.	NOVLP094/NVLS-2919
Information Disclosure Statement By Applicant		Application No.:	10/789,103
		Applicant	Wu et al.
		Filing Date	February 27, 2004
		Group	1762
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Use Several Sheets if Necessary)

U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
/J.M./	1.	7,166,531	01.2007	van den Hoek et al.			
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	3.	6,268,288 B1	07.2001	Hautala et al.			
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Other Documents

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/J.M./	18.	U.S. Office Action dated November 28, 2007, from U.S. Application No. 10/807,680 [Atty Dkt: NOVLP97/NVLS-2906]
	19.	R.J. Lewis, Sr., Hawley's Condensed Chemical Dictionary, 12 th Edition, Van Nostrand Reinhold Co., New York, 1993 (no month), excerpts pages 916-918 & 1123-1124.
	20.	Wu et al., "Methods For Producing Low Stress Porous Low-K Dielectric Materials Using Precursors With Organic Functional Groups", U.S. Application No. 11/764,750, filed June 18, 2007 [Atty Dkt: NOVLP106D1/NVLS-2930D1]
/J.M./	21.	Wu et al., "Methods For Producing Low-K CDO Films," U.S. Application No. 11/936,754, filed November 7, 2007 [Atty Docket No.: NOVLP098D1/NVLS-2907D1]

Examiner	/Julio Maldonado/	Date Considered	12/01/2008
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Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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/J.M./	22.	Wu et al., "Methods For Improving Integration Performance of Low Stress CDO Films", U.S. Application No. 11/936,752, filed November 7, 2007 [Atty Dkt: NOVLP107D1/NVLS-2932D1]
	23.	U.S. Notice of Allowance and Fee Due mailed September 27, 2007, from U.S. Application No. 11/376,510. [NOVLP099D1/NVLS-2896D1]
	24.	Allowed Claims from U.S. Application No. 11/376,510. [NOVLP099D1/NVLS-2896D1]
	25.	U.S. Notice of Allowance and Fee Due mailed September 20, 2007, from U.S. Application No. 10/941,502. [NOVLP107/NVLS-2932]
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	27.	U.S. Notice of Allowance and Fee Due mailed February 11, 2008, from U.S. Application No. 10/789,103. [NOVLP094/NVLS-2919]
/J.M./	28.	Allowed Claims from U.S. Application No. 10/789,103. [NOVLP094/NVLS-2919]

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